

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Koji NOZAKI et al

Serial No.: 09/015,287

Filed: January 29, 1998



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JUN 22 1999

GROUP ID 1700 Group Art Unit: 1752

#5/a
6/23/99
pc

Examiner: J. Cho

For: POLYMER COMPOUND FOR A CHEMICAL AMPLIFICATION RESIST AND A FABRICATION PROCESS OF A SEMICONDUCTOR DEVICE USING SUCH A CHEMICAL AMPLIFICATION RESIST

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

June 21, 1998

Sir:

In response to the Office Action dated March 24, 1999, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 6, line 36, change "includes" to --include--.

Page 9, line 35, change "contains" to --contain--.

Page 12, line 8, change "plarity" to --polarity--.

Page 14, line 5, change "azobisisobutyronitril" to --azobisisobutyronitrile--.

Page 15, line 5, change "represent" to --represents--;

line 17, change "form" to --from--.